

REMARKS/ARGUMENTS

Restriction to one of the following inventions is required under 35 U.S.C.121:

5 I. Claims 1-9, drawn to a process for depositing silicon nitride films, classified in class 427, subclass 248.1.
II. Claims 10-15, drawn to an apparatus for depositing silicon nitride films, classified in class 118, subclass 715.

Response:

10 The applicant has consequently amended the claims in the above AMENDMENTS TO THE CLAIMS section to elect claims 1-9 in invention I relating to a process of depositing silicon nitride films to be examined in the present application. Claims 10-15 are non-elected and therefore canceled.

15 Applicant respectfully requests that a timely Notice of Allowance be issued in this case.

Sincerely yours,

Winston Hsu

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25 Note: Please leave a message in my voice mail if you need to talk to me. (The time in D.C. is 12 hours behind the Taiwan time, i.e. 9 AM in D.C. = 9 PM in Taiwan.)